

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)

FIS920000237 (00750430AA)

Application Number

09/809,766

Applicant(s)

Ferrera et al.

Filing Date

03/15/2001

Group Art Unit

2881

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

P6		Goodberlet et al.; "A One-Dimensional Demonstration of Spatial-Phase-Locked Electron-Beam Lithography"; Elsevier Science B.V. - Microelectronic Engineering; 1997; pgs. 473-476
P6		Goodberlet et al.; "Extending Spatial-Phase-Locked Electron Beam Lithography to Two Dimensions"; Jpn. J. Appl. Phys., Vol. 36, Pt. 1, No. 12B; 1997; pgs. 7557-7559

EXAMINER	Paul Guzzo	DATE CONSIDERED	7/30/04
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.